



01-10-03

U.S. Application No. 09/823,196

2813

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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re United States Patent Application of:

Applicants: Thomas H. Baum et al.

Serial No.: 09/823,196

Date Filed: March 30, 2001

Title: SOURCE REAGENT COMPOSITIONS  
FOR CVD FORMATION OF GATE  
DIELECTRIC THIN FILMS USING  
AMIDE PRECURSORS AND METHOD  
OF USING SAME

Docket No.: *See OK* ATMI-510

Examiner: Erik J. Kielin

Art Unit: 2813

Customer No.: 25559

1-28-03

*L. Spruell*

TECHNOLOGY CENTER 2800  
JAN 13 2003

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**EXPRESS MAIL CERTIFICATE**

I hereby certify that I am mailing the attached documents to the Commissioner for Patents on the date specified below, in an envelope addressed to the Assistant Commissioner for Patents, Box AF, Washington, DC 20231, and Express Mailed under the provisions of 37 CFR 1.10.

*Maggie Chappuis*  
Maggie Chappuis

EV087757051US

Express Mail Label Number

January 9, 2002

Date

**RESPONSE TO JULY 9, 2002 OFFICE ACTION IN UNITED STATES PATENT  
APPLICATION NO. 09/823,196  
PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136**

Commissioner for Patents  
Washington, DC 20231

Sir:

In response to the July 9, 2002 Office Action in the above-identified application, please amend the application as follows: